CORA Cork Open Research Archive
Cartlann Taighde Oscailte Chorcaí

Title	Electrical characterization of top-gated molybdenum disulfide field-effect-transistors with high-k dielectrics
Authors	Bolshakov, Pavel;Zhao, Peng;Azcatl, Angelica;Hurley, Paul K.;Wallace, Robert M.;Young, Chadwin D.
Publication date	2017-05-05
Original Citation	Bolshakov, P., Zhao, P., Azcatl, A., Hurley, P. K., Wallace, R. M. and Young, C. D. (2017) 'Electrical characterization of top-gated molybdenum disulfide field-effect-transistors with high-k dielectrics', Microelectronic Engineering, 178, pp. 190-193. doi:10.1016/j.mee.2017.04.045
Type of publication	Article (peer-reviewed)
Link to publisher's version	10.1016/j.mee.2017.04.045
Rights	© 2017 Elsevier B.V. This manuscript version is made available under the CC-BY-NC-ND 4.0 license - http://creativecommons.org/licenses/by-nc-nd/4.0/
Download date	2026-10-31 15:17:49
Item downloaded from	https://hdl.handle.net/10468/4062

UCC
University College Cork, Ireland
Coláiste na hOllscoile Corcaigh

Accepted Manuscript



Electrical characterization of top-gated molybdenum disulfide field-effect-transistors with high-k dielectrics

Pavel Bolshakov, Peng Zhao, Angelica Azcatl, Paul K. Hurley, Robert M. Wallace, Chadwin D. Young

PII: S0167-9317(17)30190-9
DOI: doi: 10.1016/j.mee.2017.04.045
Reference: MEE 10550

To appear in: *Microelectronic Engineering*

Received date: 23 February 2017
Revised date: 10 April 2017
Accepted date: 27 April 2017

Please cite this article as: Pavel Bolshakov, Peng Zhao, Angelica Azcatl, Paul K. Hurley, Robert M. Wallace, Chadwin D. Young , Electrical characterization of top-gated molybdenum disulfide field-effect-transistors with high-k dielectrics, *Microelectronic Engineering* (2017), doi: 10.1016/j.mee.2017.04.045

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

ACCEPTED MANUSCRIPT

Electrical characterization of top-gated molybdenum disulfide field-effect-transistors with high-k dielectrics

Pavel Bolshakov[(1)*], Peng Zhao[(1)], Angelica Azcatl[(1)], Paul K. Hurley[(2)], Robert M. Wallace[(1)], and Chadwin D. Young[(1)]

[1]*Department of Materials Science and Engineering, The University of Texas at Dallas, 800 West Campbell Road, Richardson, Texas 75080, USA*

[2]*Tyndall National Institute, University College Cork, Lee Maltings Complex, Dyke Parade, Mardyke, Cork, Ireland*

*Corresponding author, pavel.bolshakov@utdallas.edu

Abstract

High quality HfO_2 and Al_2O_3 substrates are fabricated in order to study their impact on top-gate MoS_2 transistors. Compared with top-gate MoS_2 FETs on a SiO_2 substrate, the field effect mobility decreased for devices on HfO_2 substrates but substantially increased for devices on Al_2O_3 substrates, possibly due to substrate surface roughness. A forming gas anneal is found to enhance device performance due to a reduction in charge trap density of the high-k substrates. The major improvements in device performance are ascribed to the forming gas anneal. Top-gate devices built upon Al_2O_3 substrates exhibit a near-ideal subthreshold swing (SS) of ~69 mV/dec and a ~10× increase in field effect mobility, indicating a positive influence on top-gate device performance even without any backside bias.

Keywords: MoS_2; top-gated transistor; HfO_2; Al_2O_3; high-k; substrate;

ACCEPTED MANUSCRIPT

ACCEPTED MANUSCRIPT

1. Introduction

At the moment, transition metal dichalcogenides (TMDs) are one group of 2D materials that is being studied as a possible replacement for the semiconductor channel in future field-effect-transistor (FET) technology that require low power, high mobility devices[1][2][3][4]. Chief among them is molybdenum disulfide (MoS_2)[5][6], which has some of the earliest studies that report high mobility values (>200 $cm^2/V{\cdot}s$), high I_{ON}/I_{OFF} ratios (~10^8), and low subthreshold swing (~74 mV/dec) for top-gate, few-layer MoS_2 devices, usually fabricated on SiO_2/Si substrates[7]. While recent studies have demonstrated back-gate devices with HfO_2 and Al_2O_3 dielectrics[8][9][10] with high mobility values as a result of the high-k screening effect[11], few have studied the effects of these high-k dielectric substrates ("substrate" = HfO_2/Si or Al_2O_3/Si) on a top-gate devices structure akin to the silicon-on-insulator (SOI) technology in use today.

With high-k materials such as HfO_2 being utilized in current CMOS technology, their integration with TMDs can be advantageous for future applications. One recent bottleneck that has been overcome is the functionalization treatment of the inactive MoS_2 surface using a UV-ozone process that allows a uniform, high-k dielectric to be deposited[12]. With a proven top-gate MoS_2 FET fabrication process[13], an understanding of the effects of the unbiased back-gate dielectric on top-gate device performance is needed. In this paper, we demonstrate and discuss the use of high-k dielectric substrates in conjunction with a forming gas ("FG":5%H_2/95%N_2) anneal and their effect on top-gate MoS_2 devices.

2. Experimental

HfO_2 (~10nm) and Al_2O_3 (~15nm) were deposited onto Si using an atomic layer deposition (ALD) process. Metal-oxide-semiconductor (MOS) capacitors were fabricated and an FG anneal study was performed to achieve an optimal annealing temperature of 400 ^oC (1 hour) in order to establish the anneal impact on interface traps and achieve high quality dielectric substrates for top-gate devices. For the MoS_2 devices, high-k substrates used for the MOS capacitors had MoS_2 exfoliated onto them, with the source and drain patterned using photolithography and Cr/Au (20nm/150nm) deposited in a high-vacuum (10^{-6} mbar) evaporation and lift-off process. Afterwards, these back-gate devices were FG annealed at 400 ^oC, with pre- and post-anneal I-V measurements. Both sets of MoS_2 devices (HfO_2 and Al_2O_3 substrates) were then functionalized using a 15 minute, in-situ UV-ozone treatment followed by a ALD of 4nm of HfO_2 at 200 ^oC. This combination of the FG anneal and UV-ozone treatment is done to reduce any residual, process induced contamination from lithography prior to top-gate dielectric formation[14][15][16]. The last step of the process involved the deposition of a Cr/Au top gate using the same process as the source/drain, converting back-gate devices into top-gate, 3-terminal FETs as shown in Fig. 1. C-V and I-V measurements were performed using a Cascade Microtech station in conjunction with a Keithley 4200 SCS and an Agilent E4980A LCR meter.

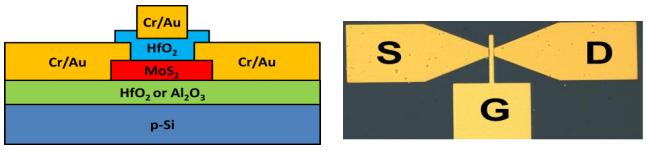


Fig. 1. Cross-section (left) and top-view (right) of the final top-gate device structure.

3. Results and Discussion

Frequency dependent C-V measurements were performed from 500Hz to 500kHz on HfO_2 and Al_2O_3 capacitors. Fig. 2 shows the low dispersion C-V curves after a 400 ^oC FG anneal, with the insets showing the high dispersion "hump" before annealing, which is typically attributed to interface traps (Q_{it}). While the dispersion in accumulation, typically attributed to series resistance (R_S), did reduce slightly after FG annealing, the Q_{it} was the most impacted by the FG annealing for both HfO_2 and Al_2O_3 as the dispersion is nearly non-existent in the depletion region post anneal.

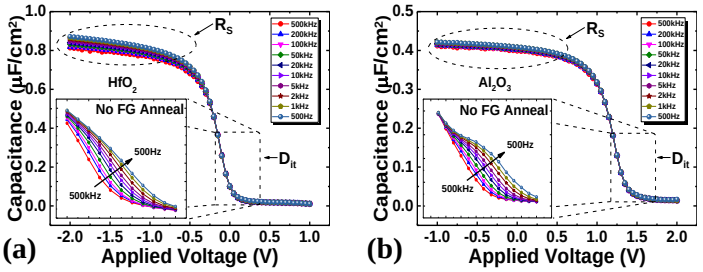


Fig. 2. C-V frequency dependence for **(a)** HfO_2 and **(b)** Al_2O_3 capacitors post 400 ^oC FG anneal with the insets showing high dispersion before annealing.

Initially, the FG annealing was performed at 200 ^oC, 300 ^oC, and 400 ^oC, and the C-V measurements were done pre- and post-anneal. Interface trap density (D_{it}) was extracted using Low-High Frequency method[17] with Fig. 3 showing the trend of D_{it} reduction as a function of FG annealing temperature. While both high-k dielectrics show a major reduction in D_{it}, the Al_2O_3 appears to have the lowest D_{it} of 2*10 cm^2eV^{-1} post 400 ^oC anneal, suggesting an Al_2O_3 substrate may yield a better interface than a HfO_2 substrate for the deposition conditions used.

ACCEPTED MANUSCRIPT

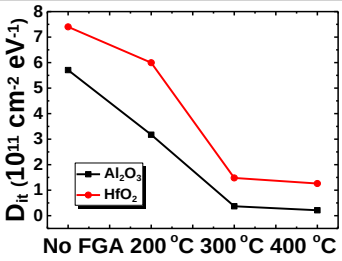


Fig. 3. Interface trap density (D_{it}) extraction shows Al_2O_3 substrates with lower D_{it} values than HfO_2 substrates as a function of FG annealing temperature.

Using HfO_2 and Al_2O_3 substrates, several back-gate MoS_2 FETs were fabricated in order to study the effect of the FG anneal on device performance and compare the substrates. As the MoS_2 flakes were untreated[18][19], their thickness was kept relatively the same (~4-5nm) in order to lower variability amongst devices. The I-V characteristics of the devices were measured pre- and post-anneal at 400 °C, with the statistics of the SS_{MIN} and I_{ON}/I_{OFF} shown in Fig. 4a. With an average I_{ON}/I_{OFF} of ~10^3 and SS_{MIN} of ~365 mV/dec pre-anneal, the performance of the HfO_2 devices improved in all instances with an average I_{ON}/I_{OFF} of ~10^5 and SS_{MIN} of ~156 mV/dec post-anneal. For the Al_2O_3 devices, with an average I_{ON}/I_{OFF} of ~10^3 and SS_{MIN} of ~207 mV/dec pre-anneal and an average I_{ON}/I_{OFF} of ~10^6 and SS_{MIN} of ~100 mV/dec post-anneal, there was also significant device improvement. This increase in performance can be attributed not only to passivation as a result of the FG anneal, but also to a possible reduction in impurities at the backside MoS_2/(HfO_2 or Al_2O_3) interface. It is worth noting that even though the net difference in device improvement was approximately the same, the post-anneal performance for devices on Al_2O_3 substrates was better than for devices on HfO_2 substrates. This may partly be as a result of better adhesion during MoS_2 exfoliation as the Al_2O_3 substrate yielded a greater number of few-layer flakes than the HfO_2 substrate, possibly due to substrate surface roughness as discussed later in this section.

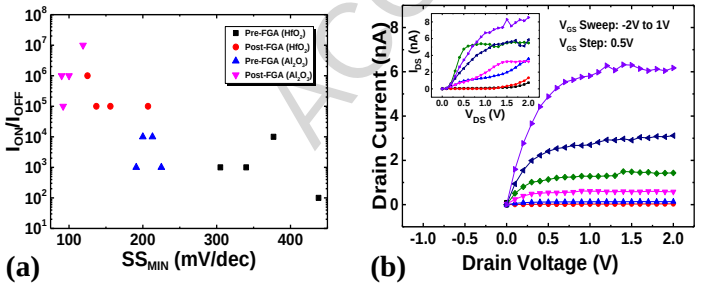


Fig. 4. (a) Several back-gate FETs on high-k substrates pre- and post-anneal indicating a beneficial trend in device performance. **(b)** I_D-V_D characteristics of a back-gate FET pre-(inset) and post-anneal indicates a beneficial effect on the contacts.

There was also a beneficial effect of the FG anneal on the contacts as (Fig. 4b) the I_D-V_D shows Schottky behavior (inset) pre-anneal and Ohmic behavior post-anneal, potentially reducing the need for sulfur passivation treatments[20][21][22]. While these back-gate devices can be useful to study the effects of the FG anneal, full device evaluation is limited, especially since current CMOS technology does no use this device structure. To properly compare the effect of the HfO_2 and Al_2O_3 substrates, a top-gate FET structure is needed.

Converting from a back-gate to a top-gate FET allows for continuous study of the same MoS_2 flake. The back-gate devices on HfO_2 and Al_2O_3 substrates, already FG annealed at 400 °C, all had UV-ozone functionalization treatment followed by in-situ HfO_2 ALD, converting to a top-gate FET with a Cr/Au (20nm/150nm) gate (Fig. 1). These devices were electrically characterized without any back-gate bias and their field effect mobility (μ_{FE}) statistics are shown in Fig. 5, along with those of top-gate devices characterized on SiO_2 substrates. There was ~10× increase in mobility for devices on Al_2O_3 substrates compared to devices on HfO_2 substrates. The HfO_2 substrates appear to have yielded devices with mobility values worse than those of devices on SiO_2 substrates.

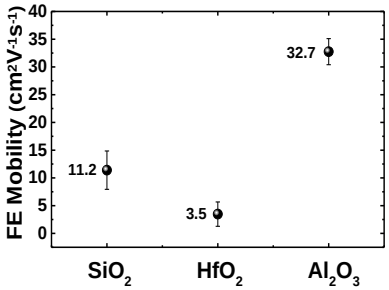


Fig. 5. Mobility statistics of multiple top-gate FETs shows a ~10× improvement in field effect mobility (μ_{FE}) on Al_2O_3 substrates over HfO_2 substrates.

Comparing the I_D-V_G of two best top-gate devices in Fig. 6, the device on a HfO_2 substrate (inset) demonstrates a poor I_{ON}/I_{OFF} of ~10 and a high SS_{MIN} of ~1400 mV/dec, while the device on an Al_2O_3 substrate demonstrates a good I_{ON}/I_{OFF} of ~10^6 and a near-ideal SS_{MIN} of 69 mV/dec. Even though the devices on both high-k substrates had good performance as FG annealed back-gate devices and went through the same top-gate conversion, those on Al_2O_3 substrates showed an improvement while those on HfO_2 substrates became worse as a top-gate device than as a back-gate device. This suggests that for MoS_2, a high-quality Al_2O_3 substrate may provide a beneficial effect to top-gate devices under the conditions stated earlier as opposed to HfO_2 substrates, with further study required for combinations of top-gate dielectrics and TMDs.

ACCEPTED MANUSCRIPT

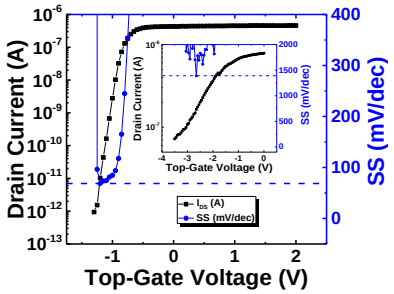


Fig. 6. I_D-V_G for top-gate FETs show a subthreshold swing (SS) from ~1400 mV/dec for a HfO_2 substrate (inset) to a near-deal ~69 mV/dec for Al_2O_3 substrate.

To determine a possible origin of the better device performance on Al_2O_3 substrates than on HfO_2 substrates, atomic force microscopy (AFM) was used to ascertain surface roughness. AFM images shown in Fig. 7 demonstrate the average RMS roughness of the Al_2O_3 substrate to be 0.19 nm, compared to 0.25 nm for the HfO_2 substrate. There are also indications of contaminants on the HfO_2 surface, most likely attributed to carbon residue[23]. The surface roughness of the backside dielectric appears to influence the exfoliated MoS_2 flake size and top-gate device performance.

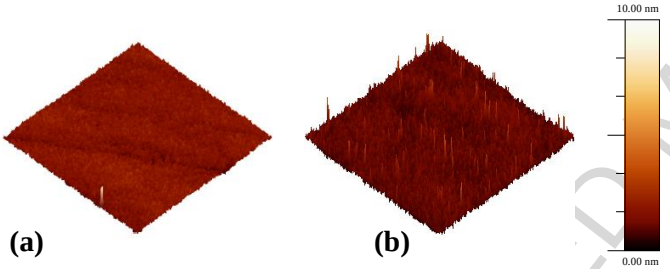


Fig. 7. AFM images of (a) Al_2O_3 substrate and (b) HfO_2 substrate with an RMS roughness value of 0.19 nm and 0.25 nm, respectively.

4. Conclusions

High quality HfO_2 and Al_2O_3 substrates were fabricated for top-gate MoS_2 field-effect-transistors and their impact on device performance was compared. A forming gas anneal was used to reduce the interface trap density and passivate these high-k substrates. The devices on Al_2O_3 substrates demonstrated much better performance compared to those on HfO_2 substrates, possibly due to substrate surface roughness. This suggests a better interface is formed between the Al_2O_3 substrate and the MoS_2 material, leading to a near-ideal substhreshold swing of 69 mV/dec for a top-gate device. This work provides insight into utilizing high-k substrates for top-gate devices in future applications of TMD materials.

Acknowledgement

This work was supported in part by the US/Ireland R&D Partnership (UNITE) under the NSF award ECCS-1407765, and the center for Low Energy Systems Technology (LEAST), one of six SRC STARnet Centers, sponsored by MARCO and DARPA.

References

[1] H.Y. Chang, S. Yang, J. Lee, L. Tao, W.S. Hwang, D. Jena, N. Lu, D. Akinwande, High-performance, highly bendable MoS2 transistors with high-K dielectrics for flexible low-power systems, ACS Nano. 7 (2013) 5446–5452. doi:10.1021/nn401429w.

[2] S. Das, J. Appenzeller, WSe2 field effect transistors with enhanced ambipolar characteristics, Appl. Phys. Lett. 103 (2013) 103501. doi:10.1063/1.4820408.

[3] L. Yu, D. El-Damak, S. Ha, X. Ling, Y. Lin, A. Zubair, Y. Zhang, Y.-H. Lee, J. Kong, A. Chandrakasan, T. Palacios, Enhancement-mode single-layer CVD MoS2 FET technology for digital electronics, in: 2015 IEEE Int. Electron Devices Meet., IEEE, 2015: p. 32.3.1-32.3.4. doi:10.1109/IEDM.2015.7409814.

[4] H. Wang, L. Yu, Y.-H. Lee, W. Fang, A. Hsu, P. Herring, M. Chin, M. Dubey, L.-J. Li, J. Kong, T. Palacios, Large-scale 2D Electronics based on Single-layer MoS 2 Grown by Chemical Vapor Deposition, (n.d.).

[5] X. Zou, J. Wang, C.-H. Chiu, Y. Wu, X. Xiao, C. Jiang, W.-W. Wu, L. Mai, T. Chen, J. Li, J.C. Ho, L. Liao, Interface Engineering for High-Performance Top-Gated MoS_2 Field-Effect Transistors, Adv. Mater. 26 (2014) 6255–6261. doi:10.1002/adma.201402008.

[6] B. Radisavljevic, M.B. Whitwick, A. Kis, Integrated Circuits and Logic Operations Based on Single-Layer MoS_2, ACS Nano. 5 (2011) 9934–9938. doi:10.1021/nn203715c.

[7] B. Radisavljevic, A. Radenovic, J. Brivio, V. Giacometti, A. Kis, Single-layer MoS2 transistors, Nat. Nanotechnol. 6 (2011) 147–150. doi:10.1038/nnano.2010.279.

[8] J. Kang, W. Liu, K. Banerjee, High-performance MoS 2 transistors with low-resistance molybdenum contacts, Appl. Phys. Lett. 104 (2014) 93106. doi:10.1063/1.4866340.

[9] T. Li, B. Wan, G. Du, B. Zhang, Z. Zeng, Electrical performance of multilayer MoS_2 transistors on high- κ Al_2O_3 coated Si substrates, AIP Adv. 5 (2015) 57102. doi:10.1063/1.4919800.

[10] K.L. Ganapathi, S. Bhattacharjee, S. Mohan, N. Bhat, High-Performance HfO2 Back Gated Multilayer MoS2 Transistors, IEEE Electron Device Lett. 37 (2016) 797–800. doi:10.1109/LED.2016.2553059.

[11] A. Konar, T. Fang, D. Jena, Effect of high- κ gate dielectrics on charge transport in graphene-based field effect transistors, Phys. Rev. B. 82 (2010) 115452. doi:10.1103/PhysRevB.82.115452.

[12] A. Azcatl, S. McDonnell, K.C. Santosh, X. Peng, H. Dong, X. Qin, R. Addou, G.I. Mordi, N. Lu, J. Kim, M.J. Kim, K. Cho, R.M. Wallace, MoS2 functionalization for ultra-thin atomic layer deposited dielectrics, Appl. Phys. Lett. 104 (2014) 111601. doi:10.1063/1.4869149.

[13] P. Zhao, A. Azcatl, P. Bolshakov-Barrett, R.M. Wallace, C.D. Young, P.K. Hurley, Top-gated MoS2 capacitors and transistors with high-k dielectrics for interface study, in: 2016 Int. Conf. Microelectron. Test Struct., IEEE, 2016: pp. 172–175. doi:10.1109/ICMTS.2016.7476201.

[14] P. Zhao, A. Azcatl, P. Bolshakov, J. Moon, C.L. Hinkle, P.K. Hurley, R.M. Wallace, C.D. Young, Effects of annealing on top-gated MoS_2 transistors with HfO_2 dielectric, J. Vac. Sci. Technol. B, Nanotechnol. Microelectron. Mater. Process. Meas. Phenom. 35 (2017) 01A118. doi:10.1116/1.4974220.

[15] A. Azcatl, S. KC, X. Peng, N. Lu, S. McDonnell, X. Qin, F. de Dios, R. Addou, J. Kim, M.J. Kim, K. Cho, R.M. Wallace, HfO_2 on UV–O_3 exposed transition metal dichalcogenides: interfacial reactions study, 2D Mater. 2 (2015) 14004. doi:10.1088/2053-1583/2/1/014004.

[16] S. McDonnell, B. Brennan, A. Azcatl, N. Lu, H. Dong, C. Buie, J. Kim, C.L. Hinkle, M.J. Kim, R.M. Wallace, HfO_2 on MoS_2 by Atomic Layer Deposition: Adsorption Mechanisms and Thickness Scalability, ACS Nano. 7 (2013) 10354–10361. doi:10.1021/nn404775u.

[17] D.K. Schroder, Semiconductor material and device characterization, IEEE Press, 2006.

[18] R. Addou, L. Colombo, R.M. Wallace, Surface Defects on Natural MoS_2, ACS Appl. Mater. Interfaces. 7 (2015) 11921–11929. doi:10.1021/acsami.5b01778.

[19] R. Addou, S. McDonnell, D. Barrera, Z. Guo, A. Azcatl, J. Wang, H. Zhu, C.L. Hinkle, M. Quevedo-Lopez, H.N. Alshareef, L. Colombo, J.W.P. Hsu, R.M. Wallace, Impurities and Electronic Property Variations of Natural MoS_2 Crystal Surfaces, ACS Nano. 9 (2015) 9124–9133. doi:10.1021/acsnano.5b03309.

[20] S. Bhattacharjee, K.L. Ganapathi, D.N. Nath, N. Bhat, Surface States Engineering of Metal/MoS2 Contacts Using Sulfur Treatment for Reduced Contact Resistance and Variability, (2015). doi:10.1109/TED.2016.2554149.

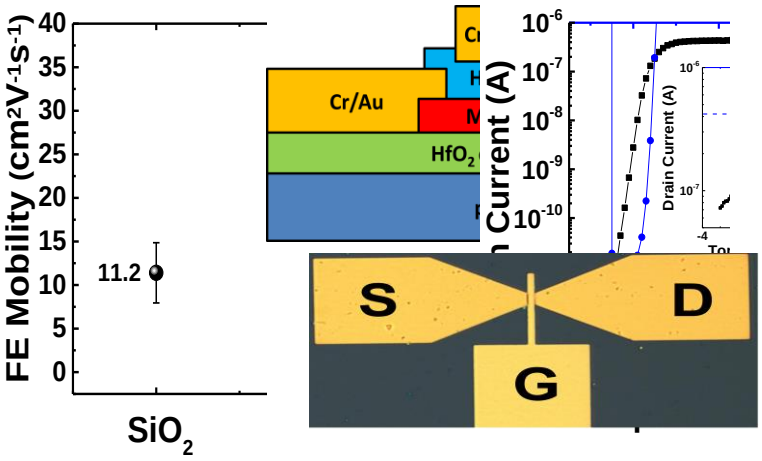
[21] K. Cho, M. Min, T.-Y. Kim, H. Jeong, J. Pak, J.-K. Kim, J. Jang, S.J. Yun, Y.H. Lee, W.-K. Hong, T. Lee, Electrical and Optical Characterization of MoS_2 with Sulfur Vacancy Passivation by Treatment with Alkanethiol Molecules, ACS Nano. 9 (2015) 8044–8053. doi:10.1021/acsnano.5b04400.

[22] M. Amani, D.-H. Lien, D. Kiriya, J. Xiao, A. Azcatl, J. Noh, S.R. Madhvapathy, R. Addou, S. KC, M. Dubey, K. Cho, R.M. Wallace, S.-C. Lee, J.-H. He, J.W. Ager, X. Zhang, E. Yablonovitch, A. Javey, Near-unity photoluminescence quantum yield in MoS2, Science (80-.). 350 (2015).

[23] X. Liu, S. Ramanathan, A. Longdergan, A. Srivastava, E. Lee, T.E. Seidel, J.T. Barton, D. Pang, R.G. Gordon, ALD of Hafnium Oxide Thin Films from Tetrakis " ethylmethylamino…hafnium and Ozone, (2005). doi:10.1149/1.1859631.

ACCEPTED MANUSCRIPT

Graphical abstract



ACCEPTED MANUSCRIPT

ACCEPTED MANUSCRIPT

Highlights

- Top-gate MoS_2 FETs were fabricated on high-k dielectric substrates
- A forming gas anneal enhances device performance with a reduction in D_{it}
- Top-gate devices on Al_2O_3/Si showed better performance than on HfO_2/Si
- AFM images suggest that substrate surface roughness affects device performance

ACCEPTED MANUSCRIPT